

2001, Vol. 4, Nr. 6, pag. G50

Self-Induced Voltage Oscillations during Anodic Etching of n-InP and Possible Applications for Three-Dimensional Microstructures

S. Langa. J. Carstensen, I. M. Tiginyanu, M. Christophersen, H. Föll

https://doi.org/10.1149/1.1370417

Abstract

Voltage oscillations were observed during anodic etching of (100)oriented n-InP substrates in an aqueous solution of HCl at high constant current density. Under certain conditions, the oscillations lead to a synchronous modulation of the diameters of pores on large areas of the samples which indicates a correlation between the phases of the oscillations in the pores. These self-induced diameter oscillations may be useful for threedimensional microstructuring of n-InP and thus for the design and fabrication of new photonic materials.